THE ELECTRICAL CHARACTERISTICS OF P-N JUNCTION FABRICATED ON N-TYPE SILICON WAFER BY USING SOLID DOPANT

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Final Year Project Report Submitted in Partial Fulfillment of the Requirement for the Bachelor of Science (Hons.) Industrial Physics in the Faculty of Applied Sciences Universiti Teknologi MARA

APRIL 2010

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Date: 13 MAY 2010

ACKNOWLEDGEMENT

Thank you Allah for gave me the spirit and strength to go through all the difficulties and problems to finish this final year project. I would like to express my gratefulness for those contributed in my Final Year Project. I would like to begin my deep gratitude to my supervisor, Ms. Farah Liyana Muhammad Khir for his valuable support, encouragement and guidance during entire project time period. The exposure and the invaluable information that you gave me really meant to me, thank you for your dedication and patience in teaching and guiding me. With my full heart, I would like to thanks to my parents and my family as they always gives me support to proceed my study and their advices that make me more confidence for future. A lot of thanks to all my friends especially my final year project's group because of their help in the process of complete my Final Year Project.

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ABSTRACT

THE ELECTRICAL CHARACTERISTICS OF P-N JUNCTION FABRICATED ON N-TYPE SILICON WAFER BY USING SOLID DOPANT

Diffusion is the major process in fabricating the p-n junction which controlled the amount of particular impurities that introduced into the semiconductor (such as Silicon) to alter the electrical characteristics by improving its conductivity. In this project, the effects of p-type dopant (Boron) diffusion into n-type Silicon wafer by using solid dopant technique were studied. The study includes fabrication, calculation and characterization of p-n junction such as sheet resistance and current-voltage (I-V) characteristics. Boron Nitride wafer is used as a solid dopant in doping process. Two stages required in this diffusion process, starts with pre-deposition and followed by drive-in diffusion at variation of temperature and time. The affects of different temperature and time onto six samples are then characterized by using Four-Point-Probe and I-V tester to determine the sheet resistance and resistance before and after the diffusion process. The result showed that sheet resistance is proportional to resistivity which is the value of sheet resistance is decrease with increasing diffusion temperature and diffusion time. Then, type of diode and its characteristics is then were identified by comparing to the theoretical value.